MODULE 3 TRANSISTOR (BJT) a 3 terminal device. These terminal Emilier and collector. It can be used well as cussent amplication. signal of small amplitude es to get magnified output collector (c). Thus it provides amplification is adrieved by passing tance to a segion of high resistance. tere the name TRANSfee - ses ISTOR In BIT, the conduction is due to both types of carriers. There are 2 types of BIT. (2) P-N-P. E DR C EONPN-OC E SYMBOL EOSTOC SYMBOZ Ea-KINO" e Hoc (2 p-n junctions are there in BJT)

2 P-N junctions ale Emetter-Base junction - JE = Cledon - Base junction - Jc ing 2 back to back diodes? (1) Relative cloping levels of B, E and C must be satisfied to work that device as a transistor. Two normal p-12 junction divdes cannot satisfy this requirement. (c) 3 a transistor E-Bjunction is forward biased vohèle B-C junction le reverse biased But due to diffusion process almost entire It reaches C and IB is negligibly small. Thus due to diffusion, the derice works as a kansistor: comite in back to back connected diddes there are 2 separente divdes, one fourand brased and other Leverse brased and diffusion cannot take place. Thus maximum series current which can flow is severse saturation current of Reverse biased (i) Emiller - Highly doped (11) Base - Lightly doped. (Higher doping than Buse) Less doping than Emittee but the collector region is more vide than E because it has to handle more

ace is beguised for heat dissipation. UNBIASED TRANSISTOR. In this case, no enternal voltage or biasing is applied. These will be no culting from any of the transistor lead. Depletion regions are created at both the junctions JE and Jc. Depletion
Regions.

E a N P N O

Jc bB JE --- B B B B + + + 00000 - - - - C 00000 - - - - C 00000 - - - - C E --- 0000 + ++ During diffusion proof depletion region penetrales more deeply into the lightly dopes side en older to include an equal numbe of impurity atoms on each side of the junction. Depletion region at JE penetuales less in the heavily doped E and entends more ento B region. Similarly depletion region at Ic penetrales less ein the heavily dope c and entends more ein the Buse region As C is slightly less doped than Emiller

the depletion layer width at Ic is more! than depletion layer with at JE. BIASED TRANSISTOR There are 3 combinations of biasing

REGION

THE FORWARD BIOISE Reverse blased 3 CUT-OFF Reverse biased Reverse biosed (3) SATURATION, Followed biased forward biased forward be ased Depending upon the enternal bias voltage poleieities, the Kansestor works in one of the 3 kegions. Ci) Active region (1) Active region Draw diagrams for cut off and saturation regions forMN and PNP Kansistons. OPERATION OF N-P-N TRANSISTOR CACTIVE REGION) JE Forward brased and Ic Leverse biased. The foeward biased E-B junction causes the elections in N type E to flow towards the B. This constitutes IE. As these electrons flow through the

Ptype B, they tend to compine with (5) holes in the Pregion (B). The B region is very their & lightly doped. Light doping means (i) Free elections have a long lifetime in the B region. In the B region. (ii) Very thin base region means the free elections have only short distance to go to reach the C, For these 2 reasons, very few of the electrons injected from Einto B recombine with holes to constitute IB. & the remaining large number of elections choss the B region and move through the c region to the + ve terminal of enternal dic source: This constitutes Ic. THE NEEN PAN James

OPERATION OF P-N-P TRANSISTOR braw diagram and write description Replaces holes for electeons & elections for holes in the description

Transistor allent Components IPE IPE-IPCI

InE Theo

Tigo

Tigo

Tigo VEB VCB Figure shows the PNP transistor with foeward biased emitter junction and the leverse brased collector junction. TE consists of hole current TPE (holes) croping from E to B) and electron current THE ( electrons arossing from B ento the E The ratio of IPE / In E cooking the JE is proportional to the Rateo of the conductivity of the p material to that of n material. Doping of E is made much larger than the doping of the base. The IE eonseits almost entirely of holes. A fews of holes crossing JE combined that also the second of the with elections in N type Base and No of them coross To. This Reduces the of holes se lost through second so lost the which ultimately seach collector To reduce the number of

lost through recombination with elections I in N region, the width of the B region is kept enteenely small. IB = IPE - FPC.

The F If the E was open circuited then IE=0 i.e. Ipc would be zero. Under this condition the B and C together act as a severse biased divide and Ic equals the severse saturation current To Ico = Inco + Ipco Inco = eaused by electors moving across Ic from P Legion to N Legion. Ipco = caused by holes moring across Jc from N region to Pregion. For a PNP fransistor IE = IB +IC

BJT CIRCUIT CONFIGURATIONS

Following de the 3 configuration

(i) common base (B (ii) Common-emille (E)

(tii) common collector (CC)

The feel common' is used to denote the transistor lead which is common to the einput and output circuits

This is Decause when a fransistor is conneded in a rigait, 4 terminals are sequiled two for input and two for output) vohile, a transestor has only teeninals. This difficulty is semoned by making one teeminal of the kansistor common to both lingut and guitput terminals The common teeminal is generally glacines ENPNTO ENTOUTH DEAN diagrams

That output input output.

Con 10 100 feausistoes. (6) Commin